

DERWENT-ACC-NO: 1994-291642

DERWENT-WEEK: 199436

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TITLE: CRT shadow mask and frame assembly with normalised drift
and improved resolution - has spaces between electron
beam apertures, near mask corner, etched to specified
depth NoAbstract

INVENTOR: KWON, S

PATENT-ASSIGNEE: SAMSUNG ELECTRON DEVICES CO LTD[SMSU]

PRIORITY-DATA: 1990KR-0020976 (December 18, 1990)

PATENT-FAMILY:

PUB-NO	PUB-DATE	LANGUAGE	PAGES	MAIN-IPC
KR 9309359 B1	September 28, 1993	N/A	000	H01J 029/07

APPLICATION-DATA:

PUB-NO	APPL-DESCRIPTOR	APPL-NO	APPL-DATE
KR 9309359B1	N/A	1990KR-0020976	December 18, 1990

INT-CL (IPC): H01J029/07

ABSTRACTED-PUB-NO: KR 9309359B

EQUIVALENT-ABSTRACTS:

CHOSEN-DRAWING: Dwg.1

TITLE-TERMS: CRT SHADOW MASK FRAME ASSEMBLE NORMALISE DRIFT IMPROVE
RESOLUTION
SPACE ELECTRON BEAM APERTURE MASK CORNER ETCH SPECIFIED DEPTH
NOABSTRACT

DERWENT-CLASS: V05

